

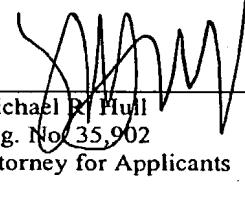


PATENT
30205/37328

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Min Ho Jung et al.)
Serial No.: 09/878,803)
Filed: June 11, 2001)
For: Additive for Photoresist)
Composition for Resist Flow Process)
Group Art Unit: 1752)
Examiner: Yvette C. Thornton)
)

I hereby certify that this paper and the
documents referred to as enclosed
therewith are being deposited with the
United States Postal Service as first class
mail, postage prepaid, on **February 27,**
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SECOND AMENDMENT AFTER FINAL (37 C.F.R. § 1.116)

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